97-0090

The invention relates to the process for materials thermic treatment and may be used in the semi-conductors engineering and microelectronics at manufacturing the apparatus and devices, optical lenses, thermal insulation materials.

The process includes the thermal treatment with further air cooling, the thermal treatment is carried out at 1100-1300°C in the antimony melt having aluminium concentration from 0,1 up to 20% of aluminium atoms.

The technical result consists in the magnesium oxide crystal lattice changing.

Claims: 1
Fig.: 2